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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Satoshi INOUE et al. Group Art Unit: 2812

Application No.: 10/748,206 Examiner: R. BOOTH

Filed: December 31, 2003 Docket No.: 040852.98

For: MANUFACTURING METHOD OF ACTIVE MATRIX SUBSTRATE, ACTIVE

MATRIX SUBSTRATE AND LIQUID CRYSTAL DISPLAY DEVICE

RESPONSE TO RESTRICTION REQUIREMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

In reply to the October 26, 2005 Restriction Requirement, Applicants provisionally elect Group II, claims 18-25 and 55-61, with traverse.

It is respectfully submitted that the subject matter of all claims is sufficiently related that a thorough search for the subject matter of any one Group of claims would encompass a search for the subject matter of the remaining claims. Thus, it is respectfully submitted that the search and examination of the entire application could be made without serious burden. See MPEP §803 in which it is stated that "if the search and examination of an entire application can be made without serious burden, the examiner <u>must</u> examine it on the merits, even though it includes claims to independent or distinct inventions" (emphasis added). It is respectfully submitted that this policy should apply in the present application in order to avoid unnecessary delay and expense to Applicants and duplicative examination by the Patent Office.

Thus, withdrawal of the Restriction Requirement is respectfully requested.

Respectfully submitted,

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Date: November 28, 2005

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